

X-ray Free Electron Laser

Part-1 Accelerator Part

XFEL Research & Development Division

RIKEN SPring-8 Center

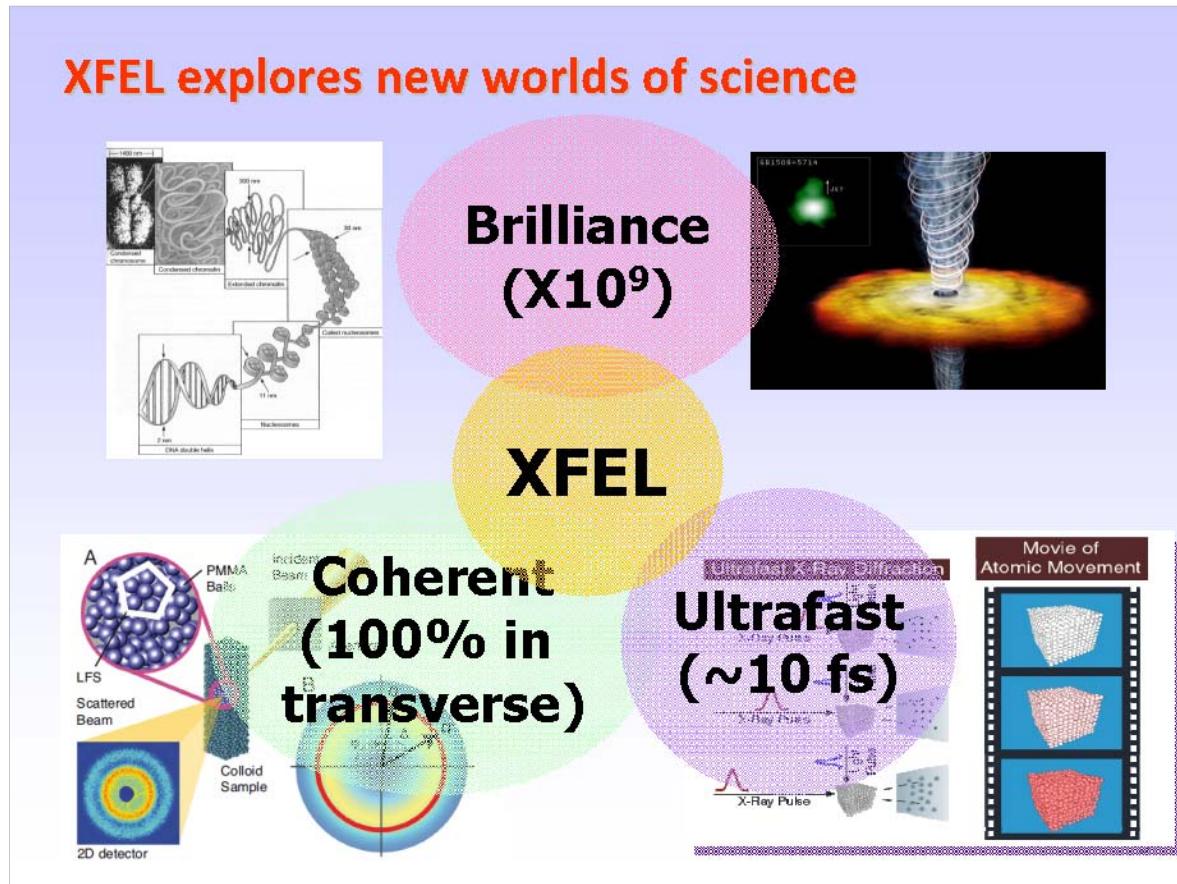
Hitoshi Tanaka

Outline

1. Introduction –What we can observe using XFEL
2. Overview of SASE XFEL
3. Approach to compact XFEL
4. Performance of XFEL

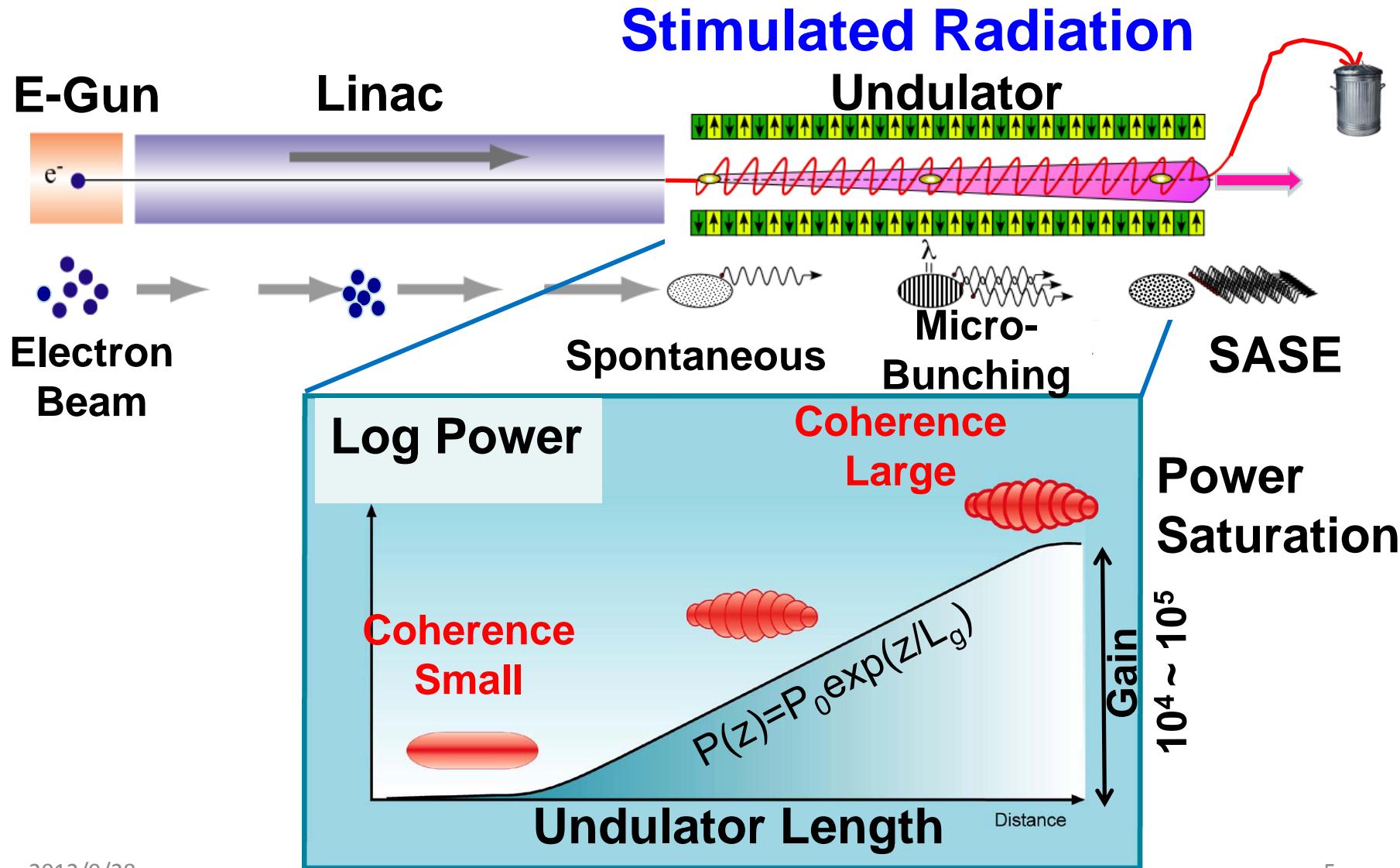
1. What XFEL enables us to observe

Key words



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2. **Overview of SASE XFEL**
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SASE XFEL Scheme

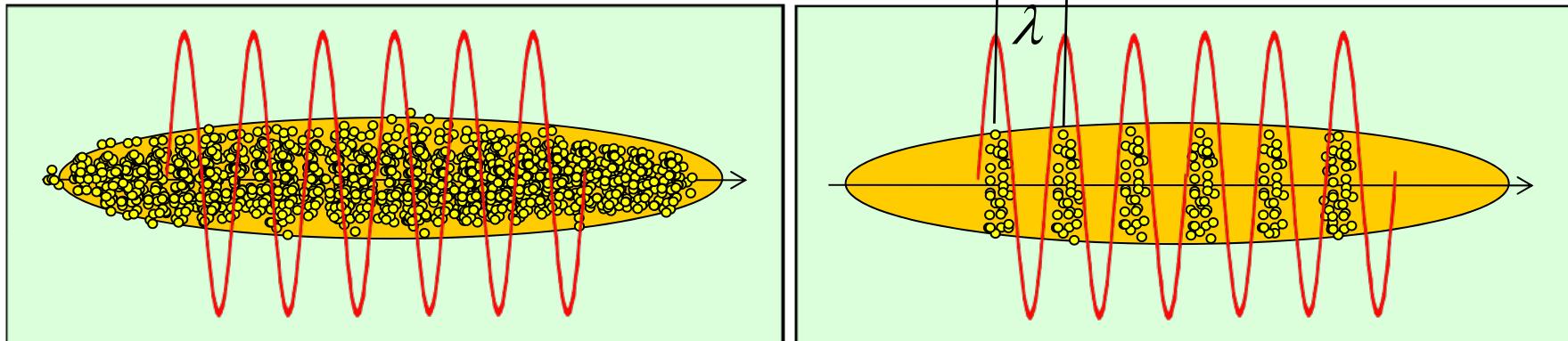


Free electrons as a laser medium

Resonance condition

$$\lambda = \lambda_u - \bar{v}_z T \approx \frac{\lambda_u}{2\gamma^2} \left(1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right), K = \frac{eB\lambda_u}{2\pi m_0 c \gamma}$$

Electron beam is trapped in an electro-magnetic potential and this potential generates energy modulation around the stable fixed point. Then the energy modulation is converted to density modulation through the energy dispersion of the undulator.



Free electrons as a laser medium

Instead of stimulated emission, the density modulated electrons with an interval of a resonance wavelength λ , enables laser amplification.

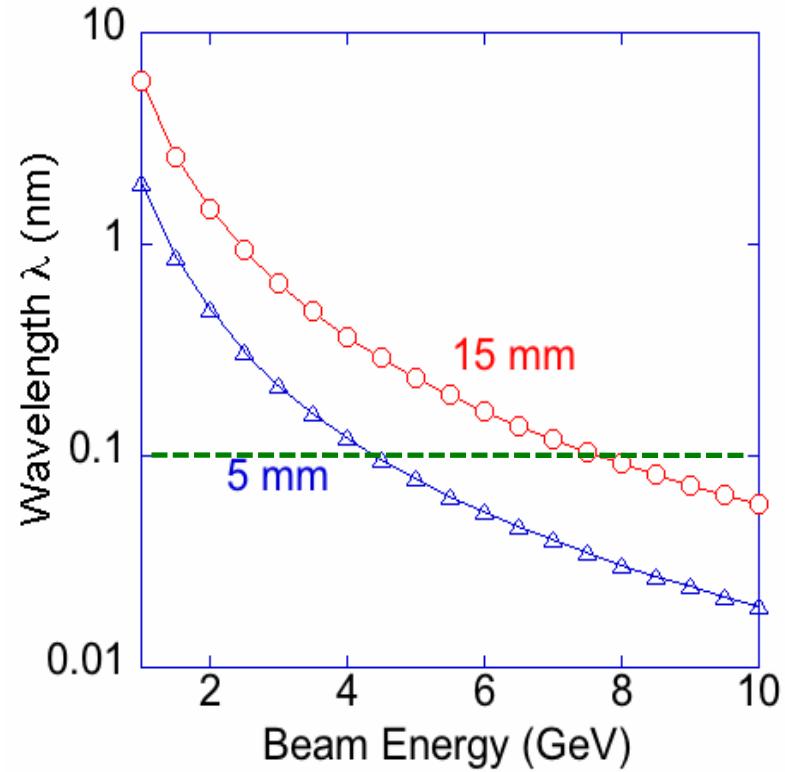
- Independent on energy level in atoms and molecules -

$$\lambda = \frac{\lambda_u}{2\gamma^2} \left(1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right), K \approx 1 \sim 2$$

Let's estimate λ assuming

$$\begin{aligned}\lambda_u &= 15 \text{ mm}, K = 2, \\ \gamma &= 3915 @ 2 \text{ GeV}\end{aligned}$$

→ $\lambda = 1.5 \text{ nm}$



Laser Amplification Gain

$$L_{1G} = \frac{\lambda_u}{4\sqrt{3}\pi\rho}, \quad \rho = \left(\frac{K}{4\gamma} \sqrt{F_1(K)} \frac{\Omega_\rho}{\omega_u} \right)^{\frac{2}{3}}, \quad \omega_u = \frac{2\pi c}{\lambda_u}, \quad n_e = \frac{N_e}{\sigma_\ell \sigma_x \sigma_y}.$$

$$F_1(K) = (J_0(\xi) - J_1(\xi))^2, \quad \xi = \frac{K^2}{2(1 + K^2)}, \quad \Omega_\rho = \left(\frac{4\pi c^2 r_e n_e}{\gamma} \right)^{\frac{1}{2}},$$

$$L_{1G} \propto \left(\frac{\langle \beta \rangle \mathcal{E}_{ns}}{I_p} \right)^{1/3}$$

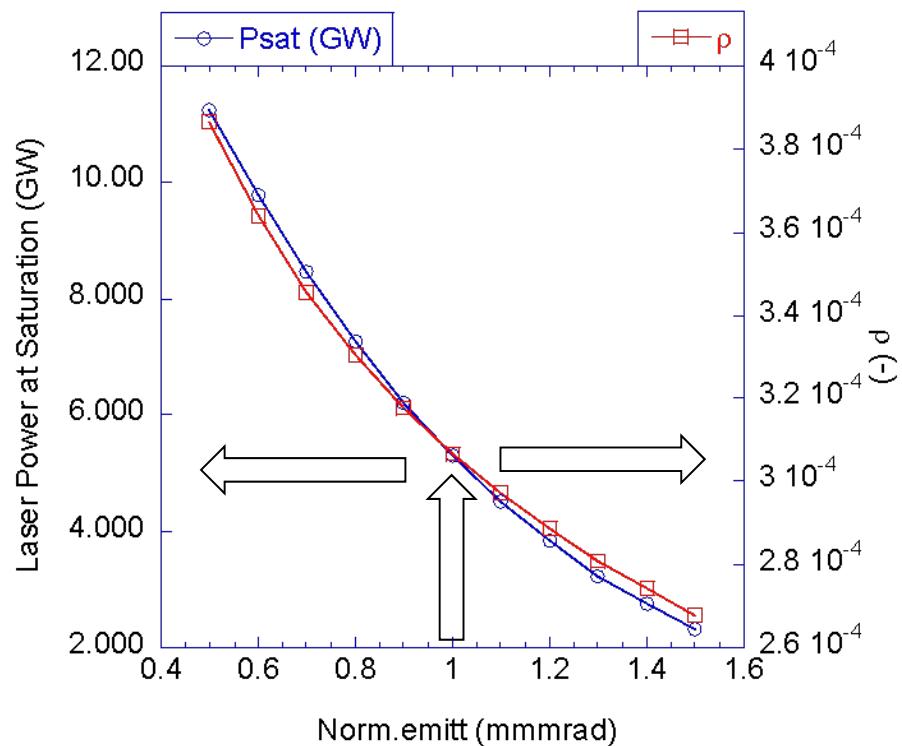
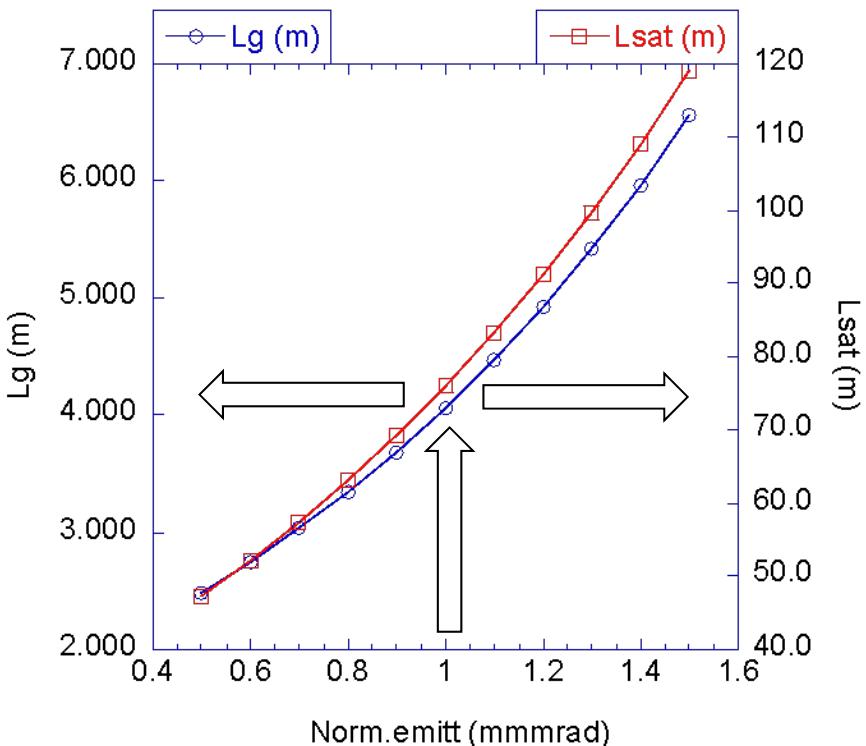
Normalized emittance at a lasing part

Peak current

For the higher gain,
smaller emittance, higher
beam current required

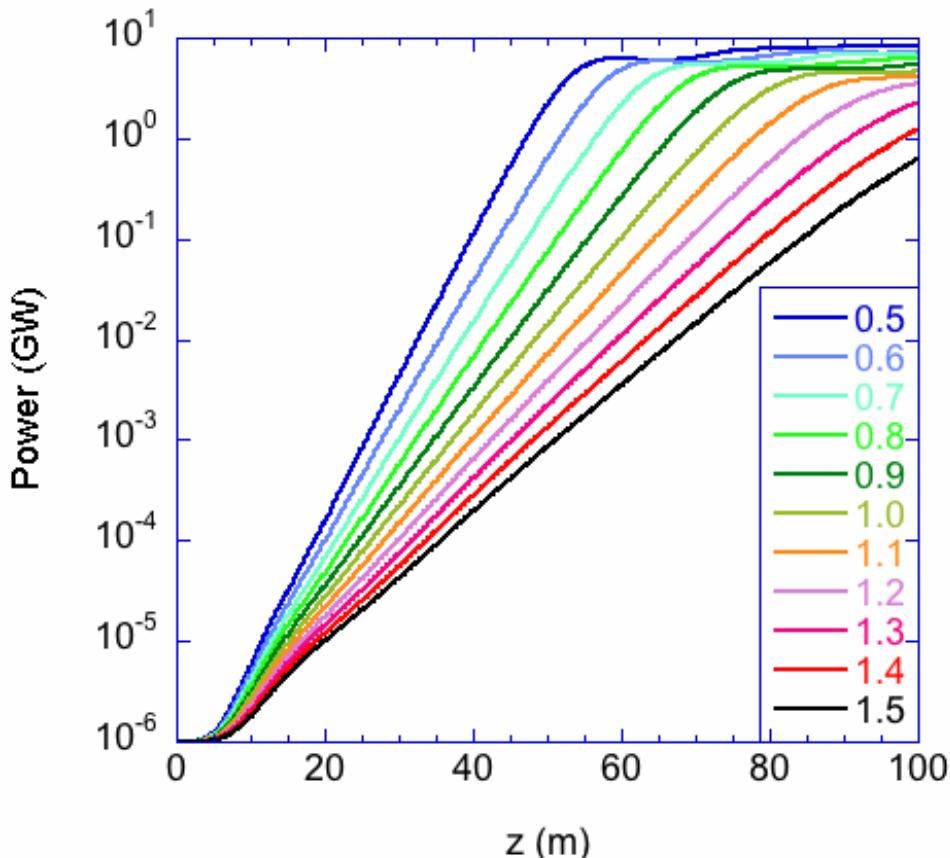
Laser Amplification Gain

$\lambda_{\text{SASE}} = 1 \text{ \AA}$, $K = 1.85$, $\lambda_u = 18 \text{ mm}$, $E = 8 \text{ GeV}$, $I_p = 3 \text{ kA}$,
 $\Delta E/E = 4 \times 10^{-5}$, $\beta_{\text{ave}} \sim 30 \text{ m}$,



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For the higher laser power, accurate overlap between laser field and electron beam along a certain distance, 15 to 25 m

Removing optical cavity system by highly brilliant electron beam + long undulator with a large number of periods

<Brilliant electron beam>

High electron density achieving a high gain and low angular divergence keeping density modulation of Å order.

<Long undulator>

A larger number of periods realizes a sufficiently high gain by a single pass, which corresponds to that obtained by the optical cavity system.

Shortening laser wavelength by high energy electron beam + short-period undulators

<High energy electron beam>

Undulator radiation wavelength depending on the inverse of gamma square

<Short period undulators>

Undulator radiation (laser) wavelength being proportional to the undulator period

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Future Perspective

Although variety of XFEL applications are expected , one facility can provide only a few BLs.

To widely utilize XFEL, it is essential to make the facility scale compact as much as we can. World's trend goes to this direction as XFEL usefulness becomes gradually clear.

Leading three XFEL

“Big three”

Euro-XFEL (2014~)

High rep rate



SASE XFELs under operation & construction in 3-sites

LCLS@SLAC(2010~)

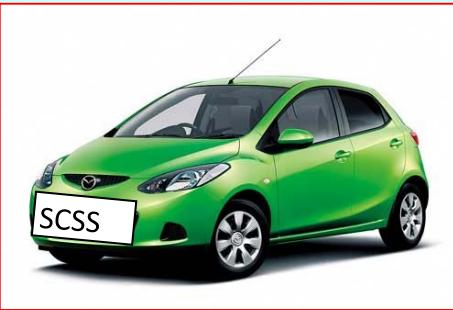


XFEL@SPring-8 (2012~)
Compact



Development Target

*SPring-8 Compact SASE Source
(SCSS) Concept*



*Compact , cheaper,
but high-performance*

versus



Wavelength of undulator radiation λ

$$\lambda = \frac{\lambda_u}{2n\gamma^2} \left(1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right)$$

To generate X-ray with **lower beam energy** requires a **shorter undulator period** and **smaller K-value** r

Design Concept of SPring-8 Compact SASE Source (SCSS)



Lower Beam Energy



Size Reduction



Efficient Acceleration



Further Size Reduction

+
Smaller
K

Smaller Normalized
Beam Emittance



Short period
in-vacuum
undulator

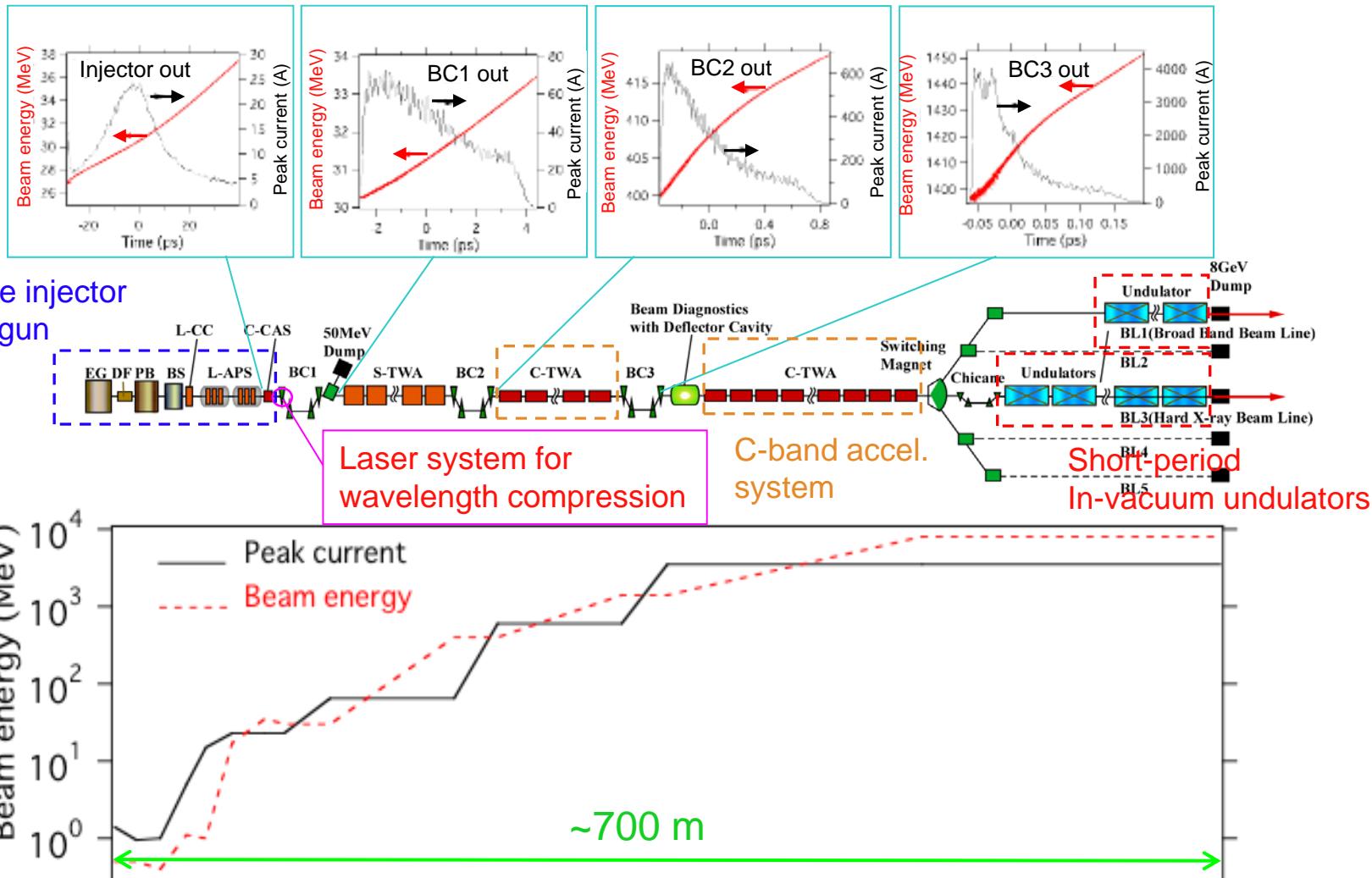


C-band high
gradient
acceleration
system



Thermionic
gun based
low emittance
injector

Compact design for 8-GeV SASE XFEL



Design Performance of XFEL

Comparison with SPring-8 performance

Parameter	XFEL	SPring-8
• Wavelength(fundamental)	>0.06 Å	>0.05 Å
• Pulse Duration	<100 fs	~40 ps
• Repitition MHz		≤ 60 Hz ~40
• Spatial Coherence	100%	~0.1%
• Peak Power	20~30 GW	100~200 W
• Peak Brilliance	~10 ³⁴	~10 ²⁴
• Averaged Brilliance	~10 ²²	~10 ²¹
Def of Brilliance : phs/sec/mrad ² /mm ²		

XFEL/SPring-8 Beamline Technical Design Report Ver. 1.0, June 17 (2008)

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